Attorney Docket No. 07303.0031 Application No. 09/759,524

AMENDMENTS TO THE SPECIFICATION:

Please amend the specification as follows:

Please replace the last paragraph starting on page 9, at line 17 with the following:

In operation, exposure apparatus 21 transfers a pattern of an integrated circuit from a reticle 80 onto semiconductor wafer 68. Exposure apparatus 21 can be mounted to a base the ground 82, i.e. the ground or via a vibration isolation system (not shown). An apparatus frame 72 is rigid and supports the components of exposure apparatus 21, including a reticle stage 76, wafer stage 66, lens assembly 78, and an illumination system 74.

FINNEGAN HENDERSON FARABOW GARRETT & DUNNER LLP

1300 I Street, NW Washington, DC 20005 202.408.4000 Fax 202.408.4400 www.finnegan.com